ABSTRACT OF THE DISCLOSURE

SUBSTRATE PROCESSING SYSTEM AND SUBSTRATE PROCESSING METHOD

A substrate-processing system has several processing units, a loading/unloading section for transferring wafers to be processed to each unit and taking out processed wafers from each unit and a sub-arm mechanism for receiving/transferring the substrates from/to the loading/unloading section and transferring the substrates one by one to each unit. The processing units and the sub-arm mechanism are controlled by a controller so that each unit processes the substrates one by one in accordance with a one-cycle time that is the maximum period among periods t1/m to tn/m obtained by dividing periods t1 to tn by the number "m" of identical units of each processing unit. The controller sets a pre-waiting time (before processing) for each processing unit.

FIG.5